

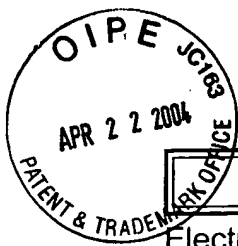


Electronic Filing System (EFS) Data
Electronic Patent Application Submission
USPTO Use Only

EFS ID: 59495
Application ID: 10608404
Title of Invention: METHOD AND COMPOSITION
FOR POLISHING A SUBSTRATE
First Named Inventor: FENG LIU
Domestic/Foreign Application: Domestic Application
Filing Date: 2003-06-26
Effective Receipt Date: 2004-04-22
Submission Type: Information Disclosure
Statement
Filing Type:
Confirmation number: 7966
Attorney Docket Number: AMAT5699P3
Total Fees Authorized: 180.0
Payment Category: Deposit Account
Deposit Account Number: 200782
Deposit Account Name: BRIAN K. HRNA
Access Code: ****
RAM Payment Status: RAM success
RAM User ID: EFSPROD
RAM Accounting Date: 2004-04-22
RAM Sequence Number: 17




Digital Certificate Holder: cn=Brian K. Hrna,ou=Registered Attorneys,ou=Patent and Trademark
Office,ou=Department of Commerce,o=U.S. Government,c=US
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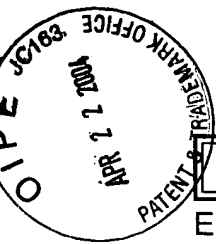


TRANSMITTAL

Electronic Version v1.1
Stylesheet Version v1.1.0

Title of Invention	METHOD AND COMPOSITION FOR POLISHING A SUBSTRATE															
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<table border="1"><thead><tr><th>Submitted by:</th><th>Elec. Sign.</th><th>Sign. Capacity</th></tr></thead><tbody><tr><td>BRIAN K. HRNA Registered Number: 41,852</td><td>[BRIAN K. HRNA]</td><td>Attorney</td></tr></tbody></table>			Submitted by:	Elec. Sign.	Sign. Capacity	BRIAN K. HRNA Registered Number: 41,852	[BRIAN K. HRNA]	Attorney								
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BRIAN K. HRNA Registered Number: 41,852	[BRIAN K. HRNA]	Attorney														
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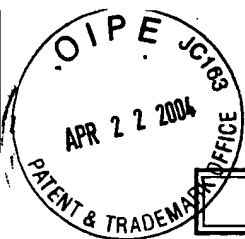
Comments



FEE TRANSMITTAL

Electronic Version v08
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Title of Invention	METHOD AND COMPOSITION FOR POLISHING A SUBSTRATE										
Application Number: 10/608404 											
Date: 2003-06-26											
First Named Applicant: FENG Q. LIU											
Attorney Docket Number: AMAT5699P3											
Art Unit: 1765											
TOTAL FEE AUTHORIZED \$180											
Patent fees are subject to annual revisions on or about October 1st of each year.											
BASIC FILING FEE											
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Submission Of Information Disclosure Stmt Fee	1806	180	180								
AUTHORIZED BILLING INFORMATION											
The commissioner is hereby authorized to charge indicated fees and credit any overpayments to:											
Deposit account number: 200782											
Access Code: ****											
Deposit name: MOSER PATTERSON SHERIDAN											
Deposit authorized name: BRIAN K. HRNA											
Signature: /BRIAN K. HRNA/											
Date (YYYYMMDD): 2004-04-22											

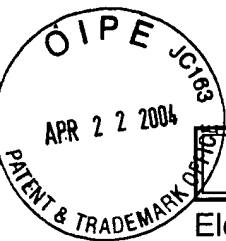


FEE TRANSMITTAL

Electronic Version v08

Stylesheet Version v08.0

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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of
Invention

METHOD AND COMPOSITION FOR POLISHING A
SUBSTRATE

Application Number: 10/608404



Confirmation Number: 7966

First Named Applicant: FENG LIU

Attorney Docket Number: AMAT5699P3

Art Unit: 1765

Search string: (6001730 or 5897375 or 5880003 or 5846882
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or 20020088709 or 20020070126 or
20020016272 or 20010024878 or
20010042690).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	6001730	1999-12-14	Farkas, et al.			
	2	5897375	1999-04-27	Watts, et al.			
	3	5880003	1999-03-09	Hayashi			
	4	5846882	1998-12-08	Birang			
	5	5783489	1998-07-21	Kaufman, et al.			
	6	5770095	1998-06-23	Sasaki, et al.			
	7	5407526	1995-04-18	Danielson, et al.			
	8	5391258	1995-02-21	Branacaleoni, et al.			
	9	5340370	1994-08-23	Cadien, et al.			
	10	5209816	1993-05-11	Yu, et al.			
	11	5114548	1992-05-19	Rhoades			
	12	4992135	1991-02-12	Doan			

	13	4934102	1990-06-19	Edson
	14	4793895	1988-12-27	Kaanta, et al.
	15	5543032	1996-08-06	Datta, et al.

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
	1	20030170091	2003-09-11	Shomler, et al.			
	2	20030153184	2003-08-14	Wang, et al.			
	3	20030136055	2003-07-24	Li et al.			
	4	20030083214	2003-05-01	Kakizawa, et al.			
	5	20030079416	2003-05-01	Ma, et al.			
	6	20030073386	2003-04-17	Ma, et al.			
	7	20020139055	2002-10-03	Asano, et al.			
	8	20020096659	2002-07-25	Sakai, et al.			
	9	20020088709	2002-07-11	Hongo, et al.			
	10	20020070126	2002-06-13	Sato, et al.			
	11	20020016272	2002-02-07	Kakizawa, et al.			
	12	20010024878	2001-09-27	Nakamura			
	13	20010042690	2001-11-22	Talieh			

Signature

Examiner Name	Date